

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Applicant(s):** Stephen W. Bedell, et al.

**Examiner:** Unassigned

**Serial No.:** To be assigned

**Art Unit:** Unassigned

**Filed:** Herewith

**Docket:** YOR920030203US1 (16694)

**For:** FORMATION OF A SILICON  
GERMANIUM-ON-INSULATOR STRUCTURE  
BY OXIDATION OF A BURIED POROUS SILICON LAYER

**Dated:** September 12, 2003

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**PRELIMINARY AMENDMENT**

Sir:

In connection with filing the above-identified application under 37 C.F.R. §1.53(b), applicants submit the following amendments and remarks for consideration by the Examiner and entry of record in the above-identified patent application.

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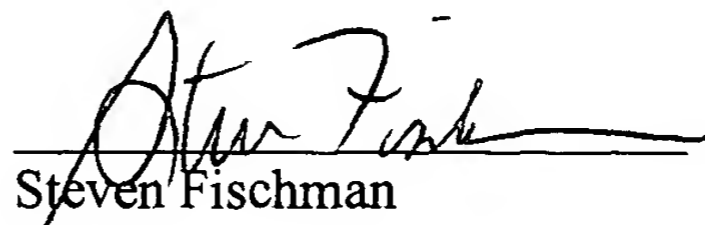
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Dated: September 12, 2003

  
Steven Fischman